



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

MOORS et al.

Appln. No.: 09/934,698

Filed: August 23, 2001

Confirmation No.: 8408

Group Art Unit: 2851

Examiner: Hung Nguyen

Title: MASK HANDLING APPARATUS, LITHOGRAPHIC PROJECTION APPARATUS,
DEVICE MANUFACTURING METHOD AND DEVICE MANUFACTURED THEREBY

December 16, 2002

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AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated September 16, 2002, please amend the above
identified application as follows:

IN THE SPECIFICATION:

Page 20, delete the whole paragraph starting at line 8 and replace it with the following
new paragraph:

In an eleventh embodiment, which is illustrated in Figs. 15a and 15b, particles are
prevented from colliding with and sticking to the mask MA in a lithographic apparatus, a
mask handling apparatus or a mask storage box by providing a temperature difference
between the mask and its surroundings.

Page 20, delete the whole paragraph starting at line 12 and replace it with the
following new paragraph:

The temperature difference can be provided by providing a heater 55, e.g. a lamp, to
heat the mask and/or by providing a cold plate 56, cooled by a suitable cooler 57, in the
vicinity of the pattern surface of the mask MA. The presence of a cold surface near the mask
reduces particle adherence to the mask because particles colliding with the cold surface will

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